

## Nanofocus Electron Sources

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## EF-15005

This electron gun column is designed to generate a very small spot in the nm range. It is also available as part of a complete scanning electron imaging package (SEM-package).

### Key features

- Beam size (min.) <85 nm at max energy and 12 mm working distance
- Energy range 200 eV – 15 keV
- Beam current (max.) 1  $\mu$ A

### Characteristics

- Working Distance (WD) 10 mm – 50 mm
- Optimum WD 12 mm nominal
- [Basic beam blanking \(optional\)](#)
- [Beam blanking, external \(optional\)](#)
- [Beam pulsing \(optional\)](#)
- [Computer control \(optional\)](#)
- [Magnetic shielding \(optional\)](#)
- [Beam scanning \(optional\)](#)
- [Microprocessor controlled beam current regulation \(optional\)](#)
- Remote control



Not all parameters can be reached simultaneously. Above specifications may change without notice. Pictures / diagrams for reference only.

### Typical Applications

[AES- Depth profiling](#)

### Related Products

[Filaments](#)



- Sources
- > Electron Sources for RHEED
- > Accessories for Electron Sources
- > Ion Sources
- > X-ray Source
- > Energy Analyzers & Imaging Energy Filters
- > Charged Particle Detectors
- > PEEM & IEEM
- > UHV-Systems for Surface Analysis
- > Packages for Surface Analysis
- > Data Acquisition & Instrument Control Software

- Absorbent current EM (electron microscope)
- [Elastically scattered EM \(electron microscope\)](#)
- UHV Scanning Electron Microscopy (SEM)
- Scanning Auger Microscopy (SAM)
- Auger Electron Spectroscopy (AES)
- Electron Energy Loss Spectroscopy (EELS) / Reflection Energy Energy Loss Spectroscopy (REELS)
- Sample imaging
- Electron Backscattered Diffraction (EBSD)
- X-ray emission analyses

- Pre-mounted, pre-aligned cathode units
- Complete service kit
- Diagnostic box
- Scan amplifier
- Faraday cups
- Sample current measurement kit
- Gun control module
- AES and XPS energy spectrometers (ESA and DESA)
- Secondary Electron Detectors (SED) for imaging
- Scanning and imaging package (SEM Package)
- EBSD energy filter and detector

## PRODUCTS

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- > AUGER / XPS / EELS / REELS
- > Electron Sources
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## APPLICATIONS

- > *In situ* Characterization
- > Surface Analysis Techniques
- > Material Growth Monitoring
- > Electron Diffraction
- > Scanning Electron Microscopy
- > Photoelectron Microscopy (PEEM)
- > Depth Profiling
- > Space Environment Simulation
- > Surface & Materials Modification

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